Master: Primary flow channelwidth = 100 um

Clean :

* ddH2O
* Acetone
* (Sonication, 10 min)
* Dehydration ( ***15*** *min* @ **120**°C )

Spin :

* ***HTexture*** **2** = ***15 μm***

Photoresistor: negative **Su-3010**

|  |  |  |  |
| --- | --- | --- | --- |
|  | *Speed* | *ramp* | *Time* |
| 0° | 500 rpm | 1 | ***10*** *s* |
| 1° | 1000 rpm (15 um) | 1 | ***30*** *s* |

Soft Bake : 1 min @ 65°C **+** ***10*** *min* @ **95°**C

Exposure : E20 = **200** [mJ/cm^2]  ≈ *s*

Post Bake :

|  |  |  |
| --- | --- | --- |
| ***65****°C* | *ramp* | ***95****°C* |
| ***1*** *min* | ***5*** *min* |

Develop : t = ***6*** *min* Hard Baking : about ***20*** *min*  @ ***200°***C